

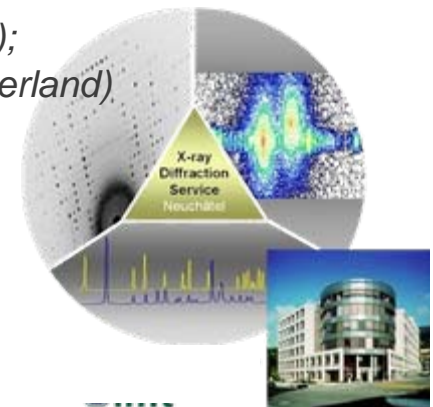
Failure Mode Discussion on Irradiated MEMS Structures

Alex Dommann¹; Antonia Neels¹; Herb Shea²; Grégoire Bourban², Andreas Schifferle³

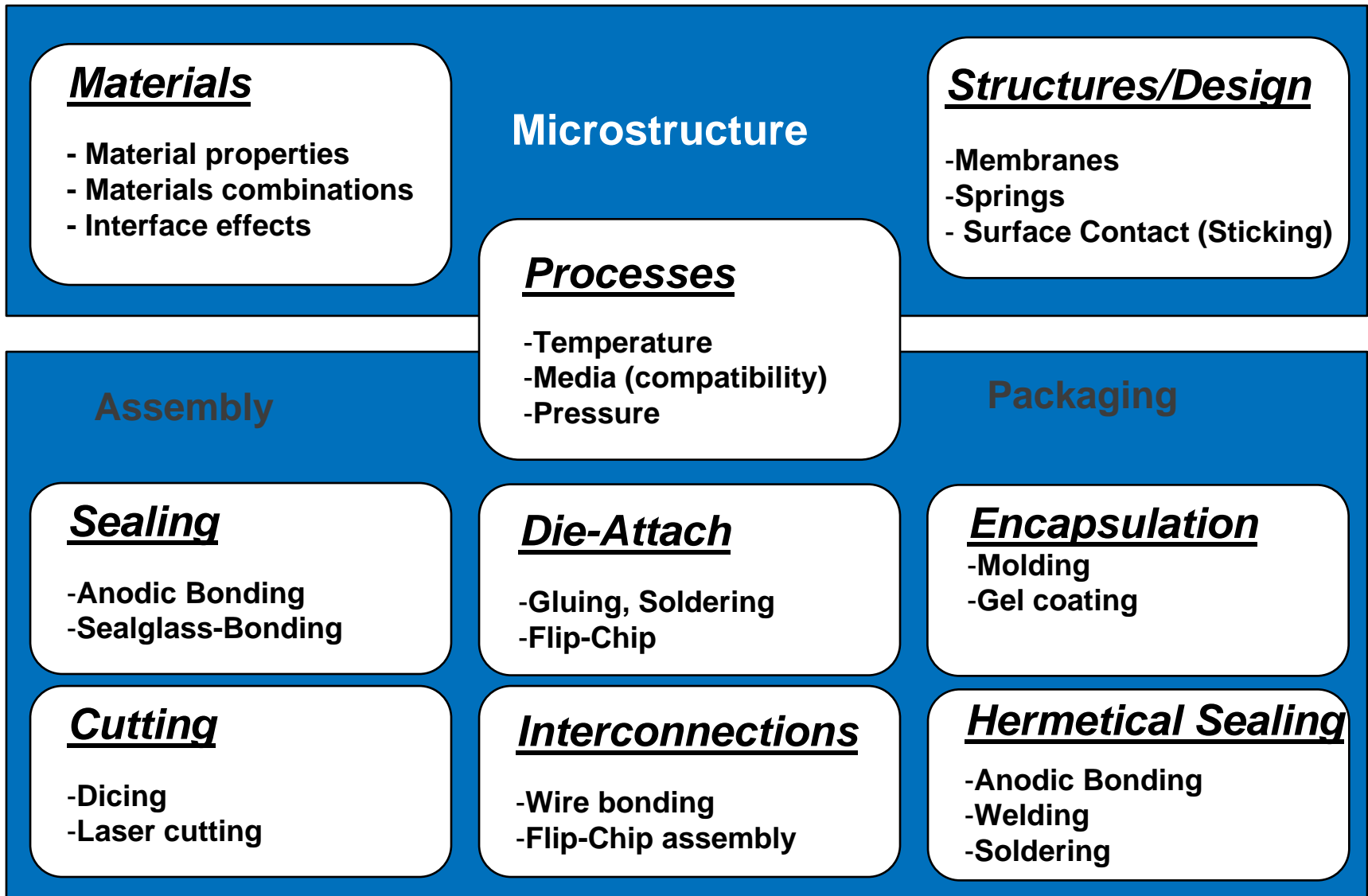
¹CSEM, Microsystems Technology (Switzerland);

²EPFL, Microsystems for Space Technologies Laboratory, (Switzerland)

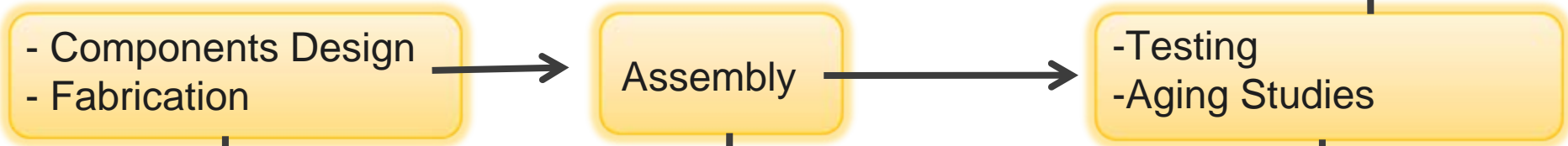
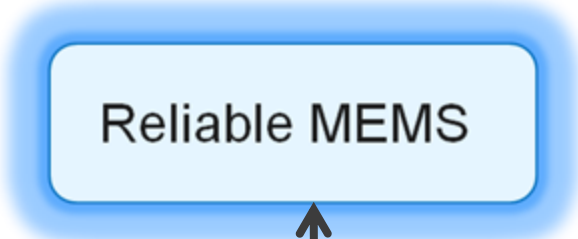
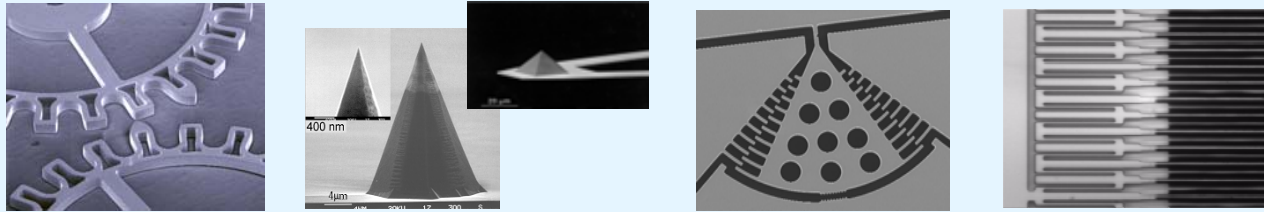
³ETHZ, Institut für Mechanisch Systeme, (Switzerland)



Quality Control & Reliability of MEMS



Reliable MEMS



Components characterization:

- structural analysis: phases, texture, strain, ...
- defect and strain analysis related to MEMS parts in fabrication processes

Packaging:

- defect + strain analysis

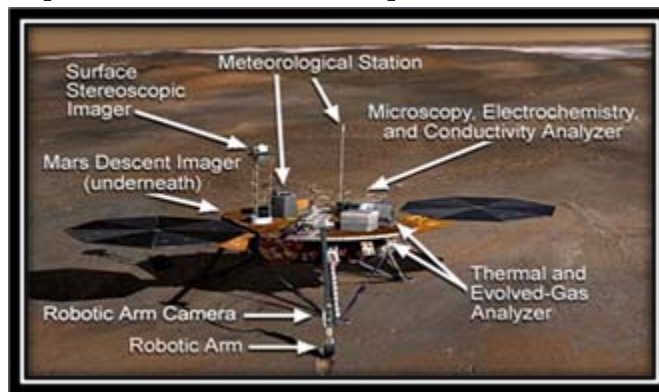
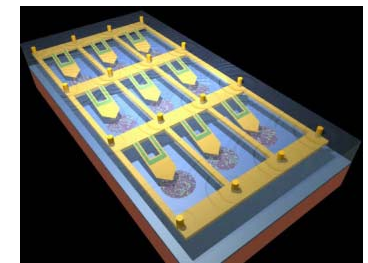
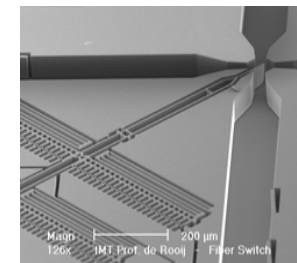
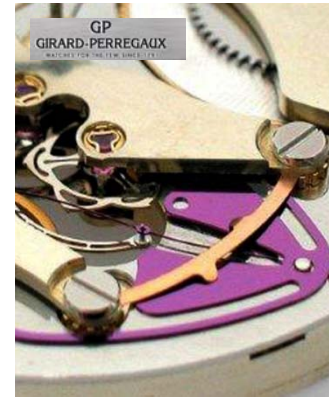
Mobility of Defects:

in-situ testing:
structural + mechanical

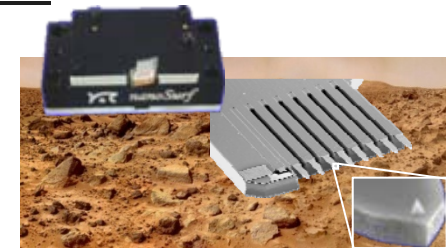
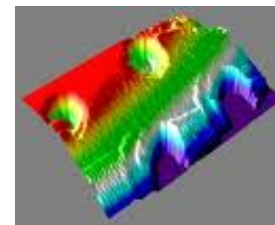
-aging studies:
T, radiation, high cycle fatigue

Foundry Services

- Watch Parts
- Optical MEMS Switches and Nanotools
- Components for Space Research



Phoenix Mars Mission



Multiple sensors on the AFM probe various samples of the Martian soil.

Some examples



Study of functional (mechanical) properties related to defect dynamics in MEMS:

Dynamical Studies

Testing / Aging

Temperature
Influence

Radiation
Damage

Mechanical Testing

In-situ Tensile
and Bending
Tests

High Cycle
Fatigue on
MEMS

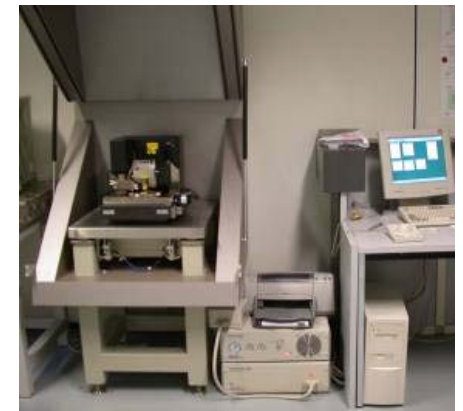
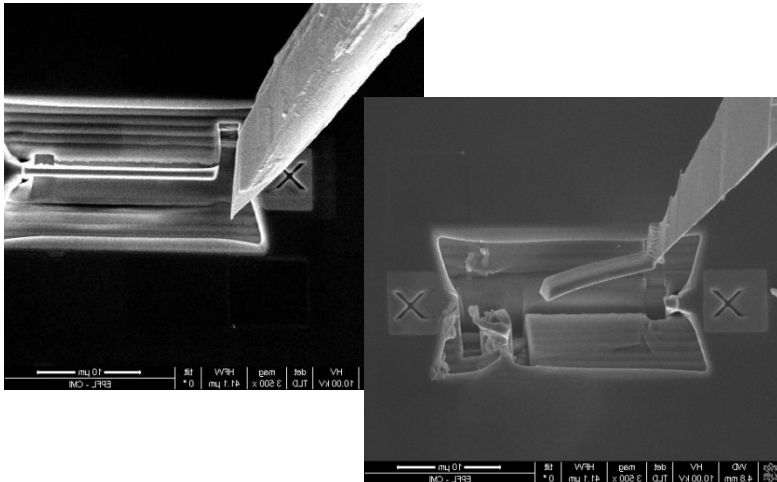
Defect Analysis in SiSC MEMS

X-ray Diffraction

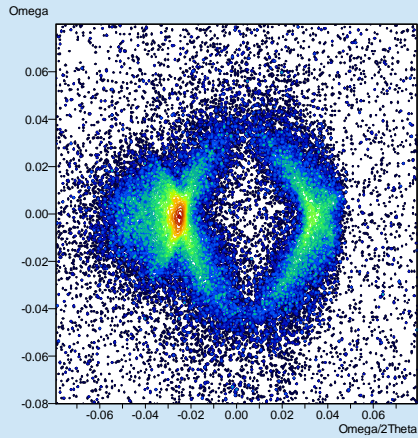
- HRXRD (global defect analysis)

Microscopy

- AFM (surface defects)
- FIB + TEM (defect profile in cross section)

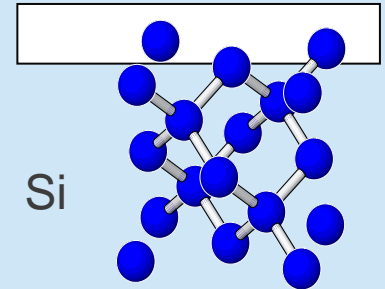


HRXRD



Characterization

Functional: electrical, mechanical
Structural



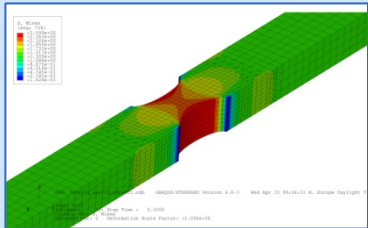
+

Reliability
in MEMS

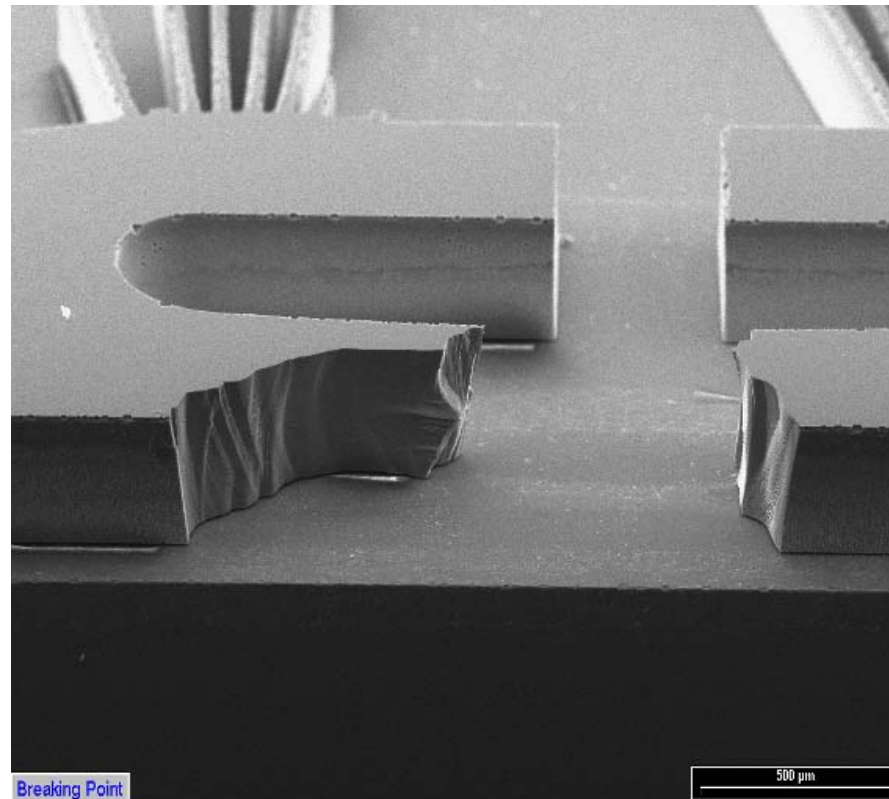
Mechanical:
Bending + tensile tests

Simulations

Testing

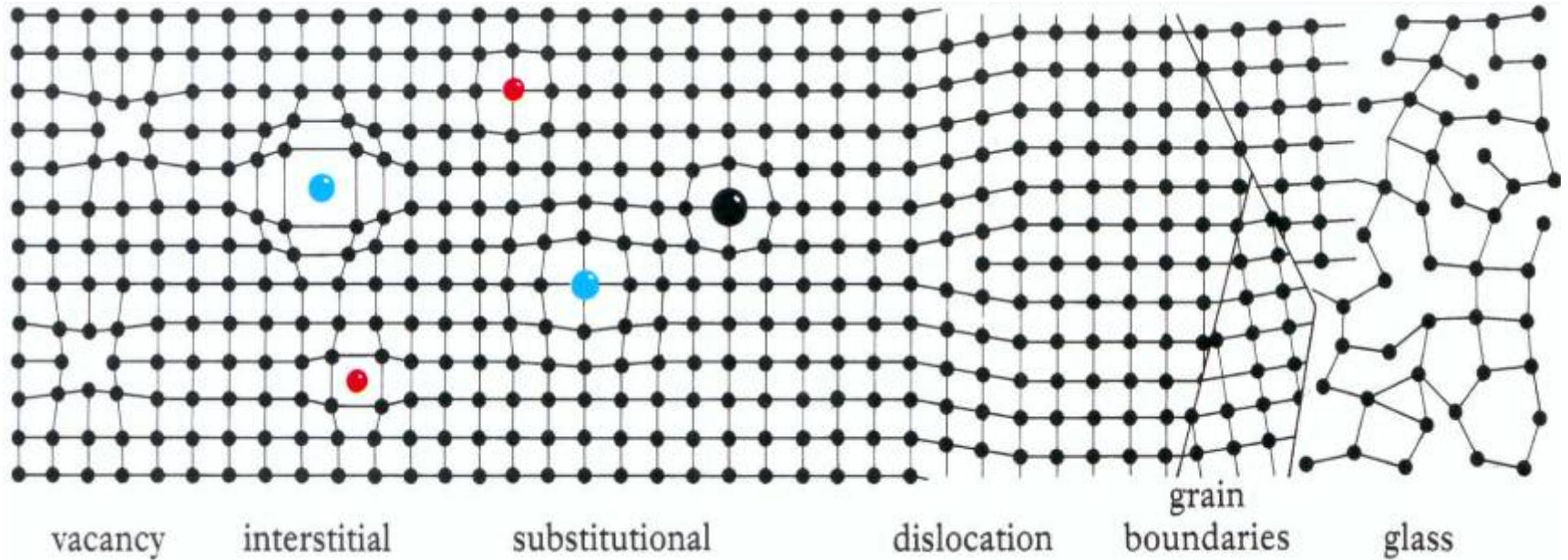


Study of materials properties: fracture toughness



When SiSC structures break ?
Why SCSi structures break ?

Defects in a Crystal



from: I.F. Mercer: "Crystals", The Natural History Museum, London 1994

+ surface defects (roughness, ...)

+ sample size effect

Analysis Infrastructure at CSEM

AFM



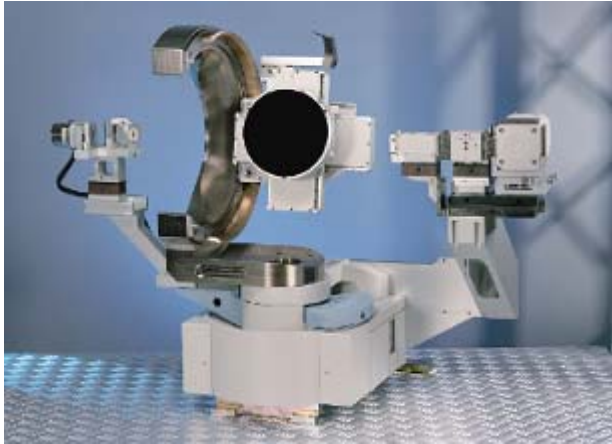
ESEM



RBS

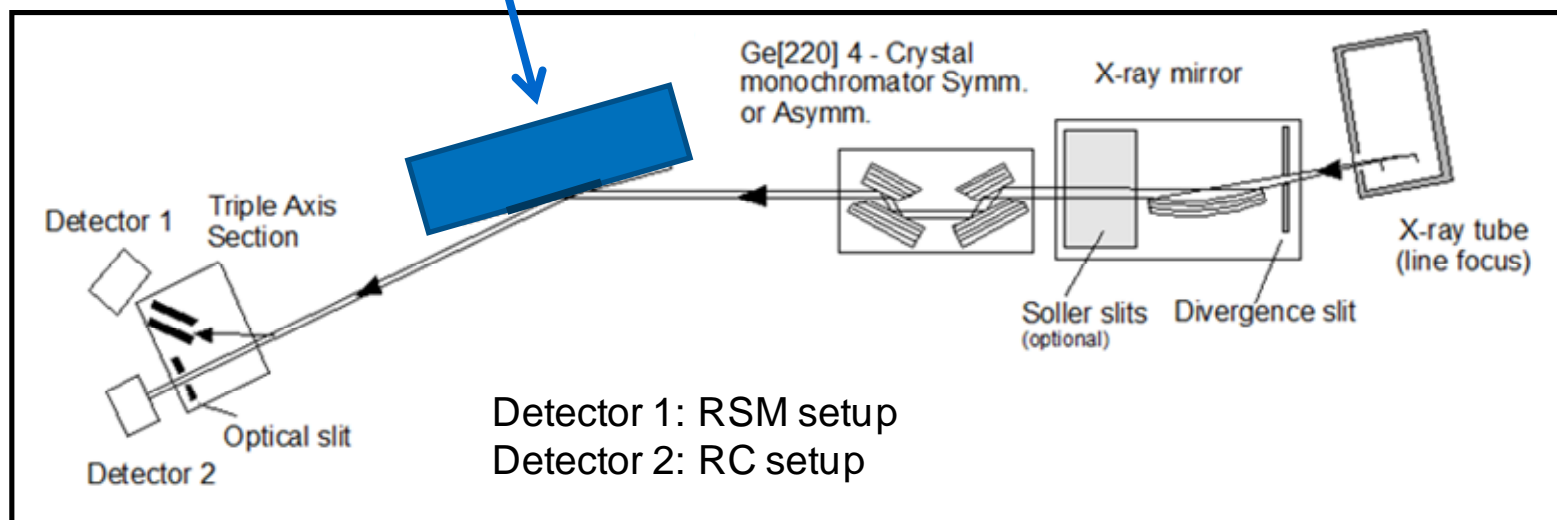


HRXRD



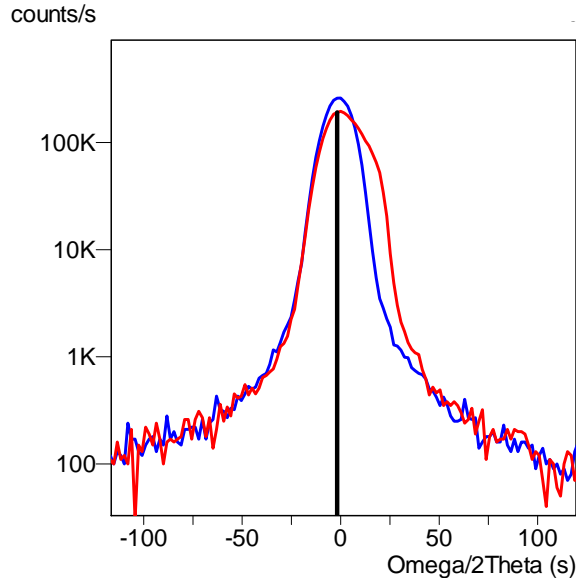
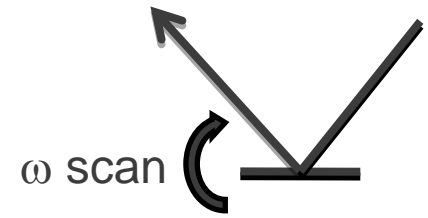
HRXRD on SCSi MEMS

Mechanical Test Instrument with the sample also positioned with respect to the diffractometer setup:



PANalytical X'Pert PRO MRD

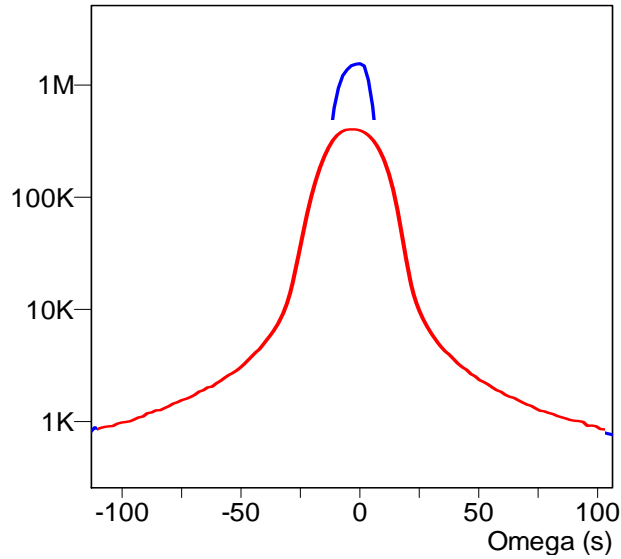
X-ray Rocking Curve (RC) measurements



1. Strain

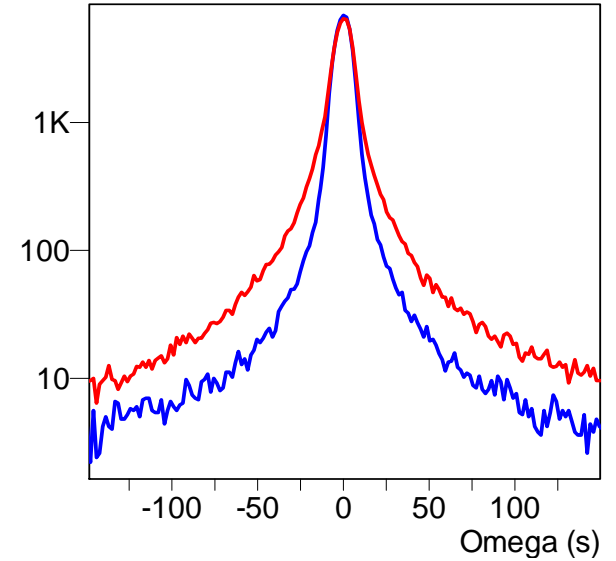
$$\varepsilon = \Delta d/d = -\Delta\theta/\tan\theta$$

$$\delta = E \varepsilon$$



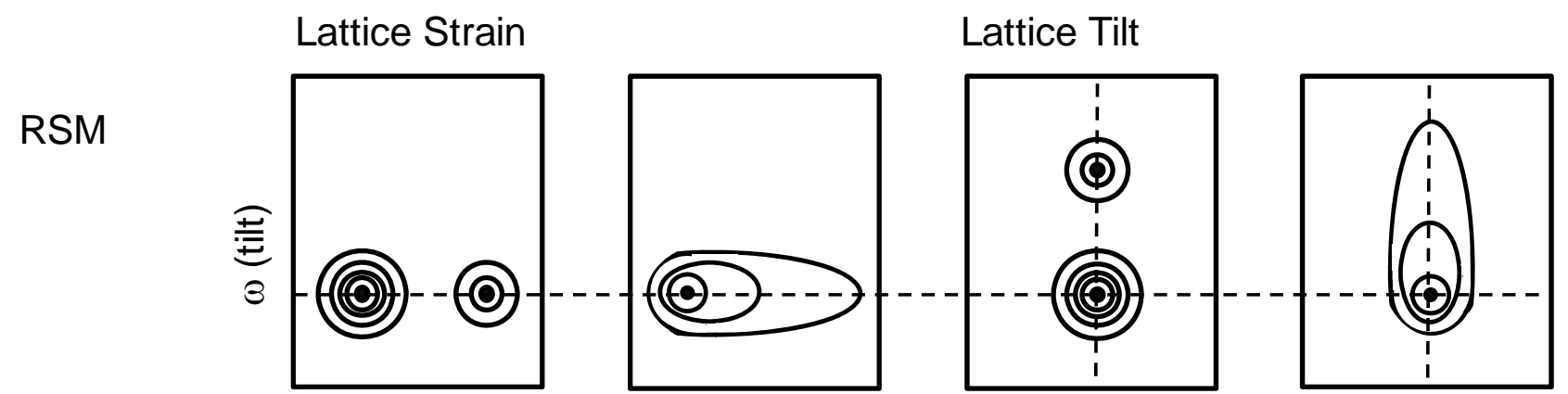
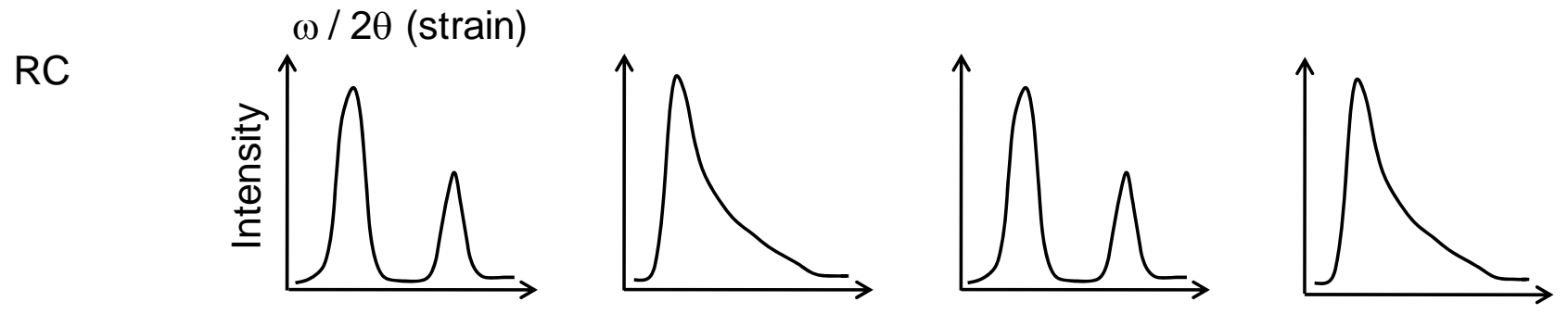
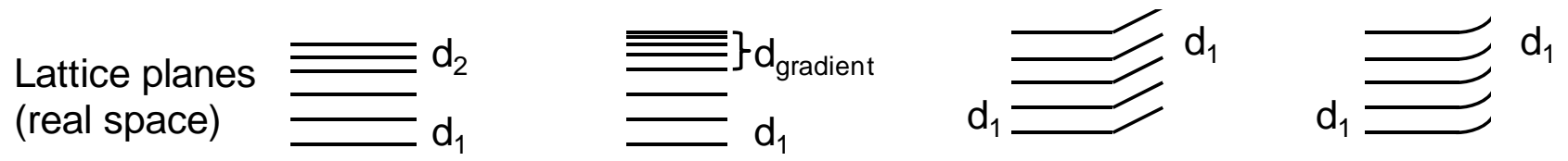
2. Curvature

■ reference



3. Defects from diffused scattering

HRXRD for strained layers

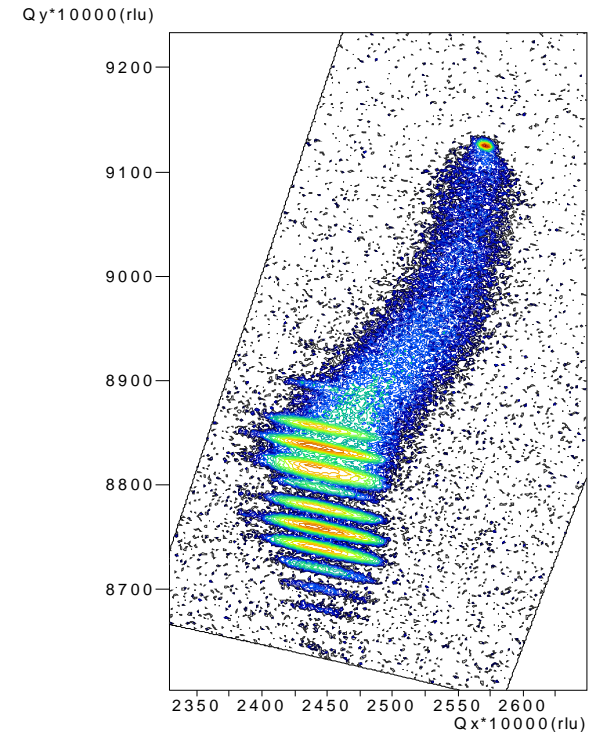


Reciprocal Space Mapping (RSM)

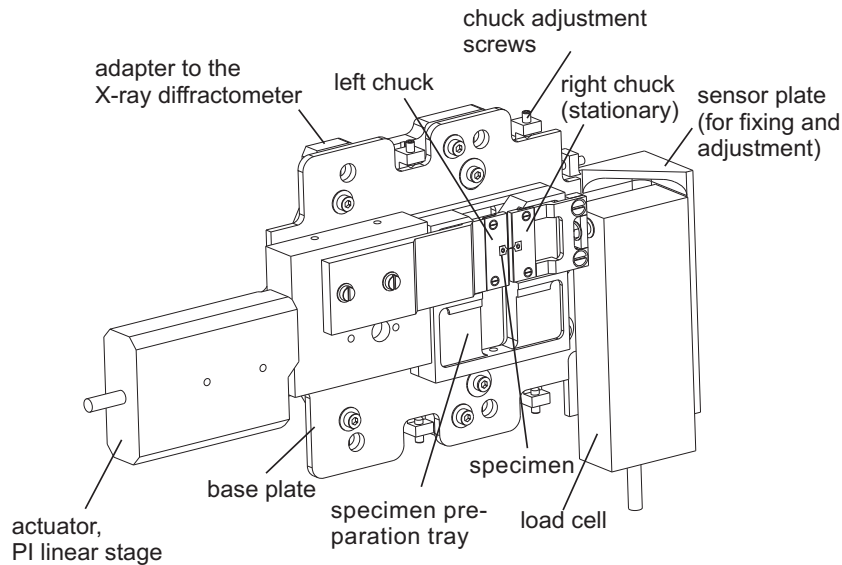
Scattering close to the maximum of a nearly perfect sample can be separate into distinct features:

- Bragg scattering
- surface truncation
- dynamical streak
- diffused scattering (defects in material)

The information of the sum of defects is found.

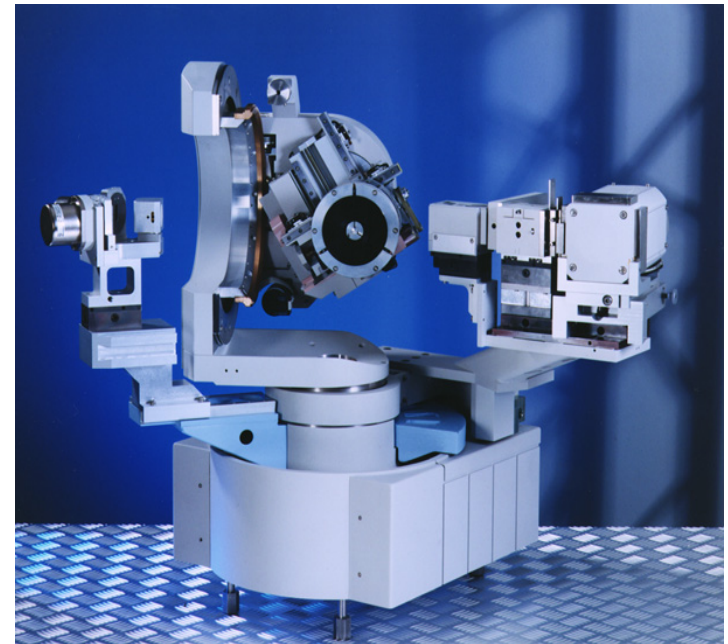


Bending Test + Tensile Test Instrument: easily adjustable

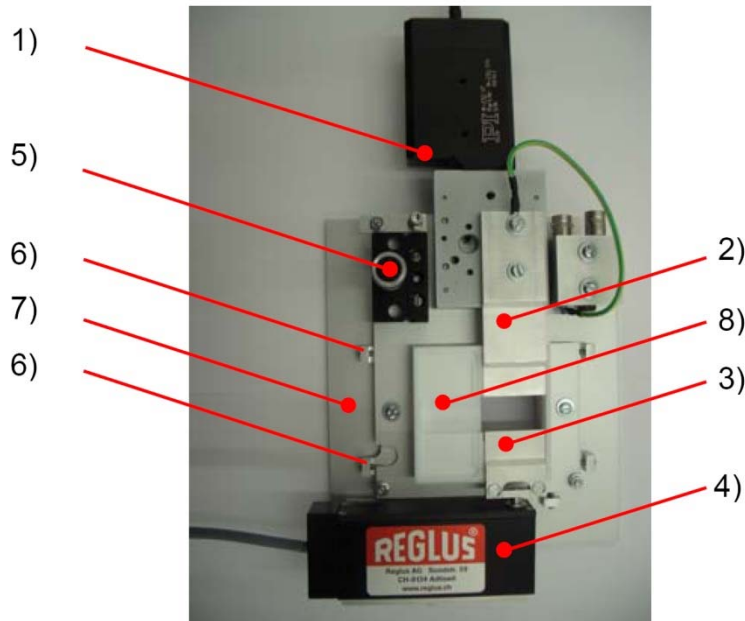


Mounting for In-situ Testing

Structural Analysis by HRXRD

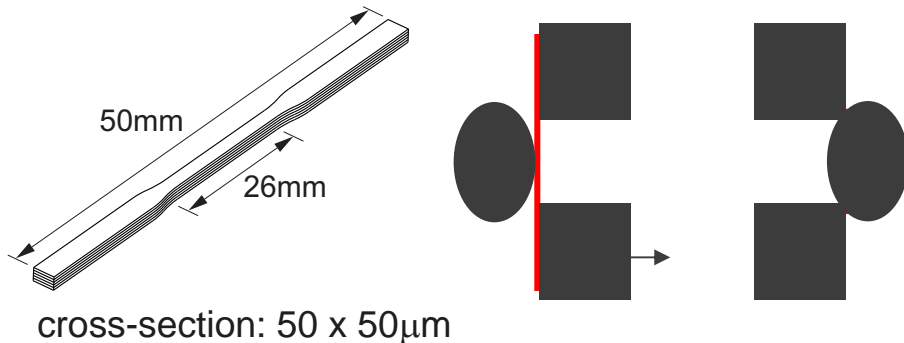


Development for in-situ testing:

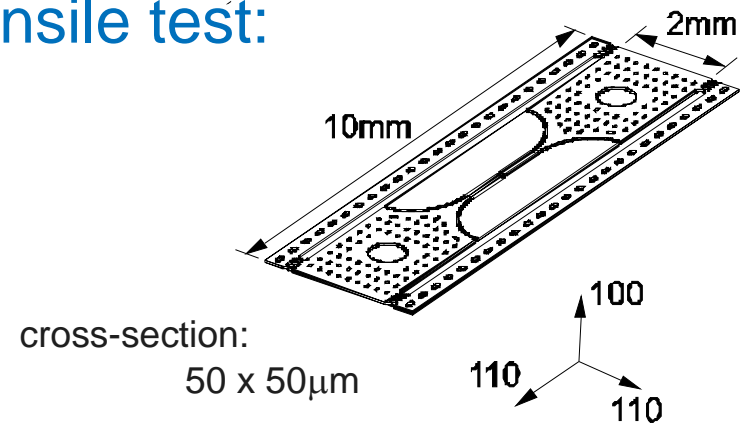


- 1) Actuator motor
- 2) Moving support (16 mm)
- 3) Static support
- 4) Force sensor (2 N)
- 5) Manual position adjustment
- 6) Fixation force sensor
- 7) Support frame
- 8) Probe holder

Two point bending test:

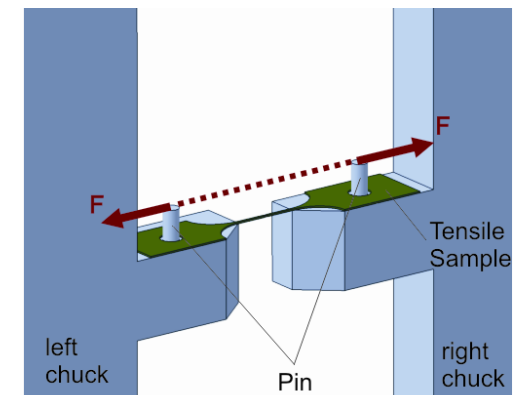
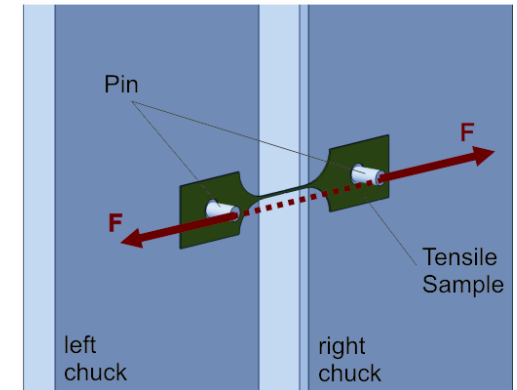
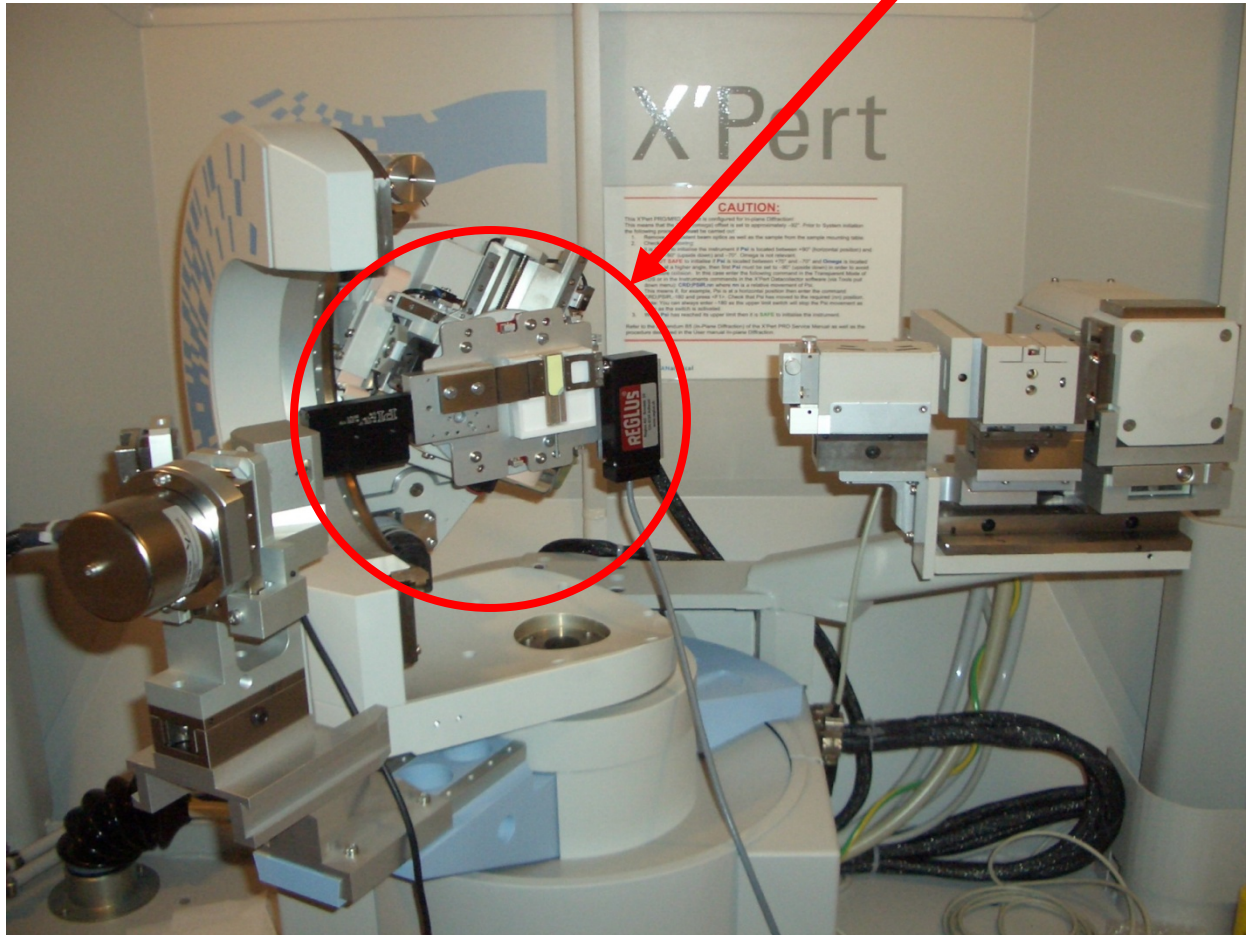


Tensile test:



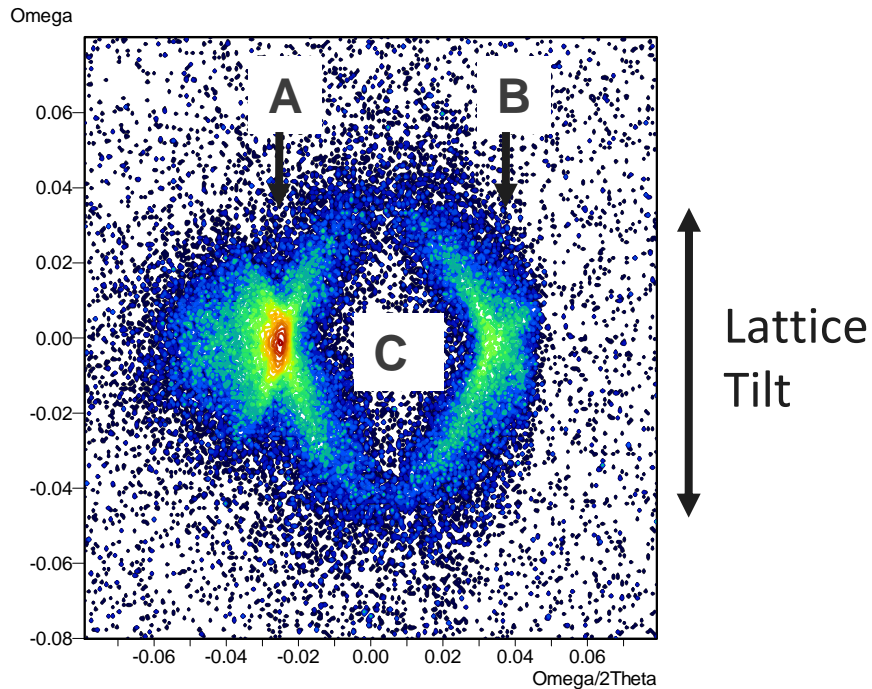
Tensile test: set-up

In-situ mechanical testing :
strain and defect analysis



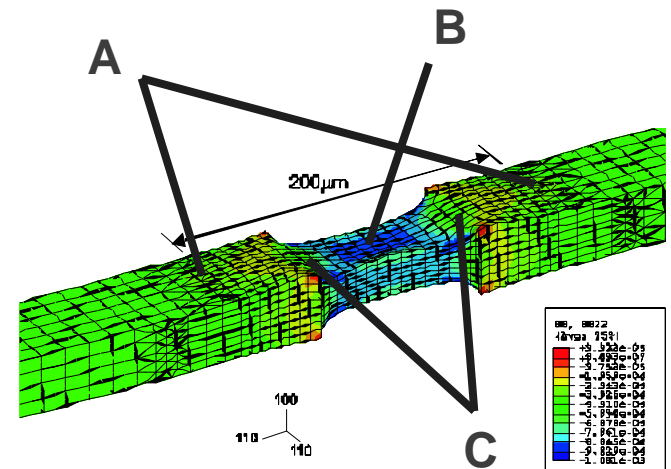
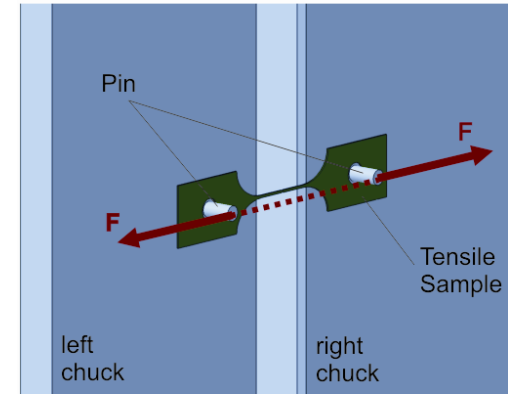
Mechanical Testing: In-situ Tensile Tests on SiSC micro-beams

Example of a tensile test on SCSi (single crystal, 50µm beam)

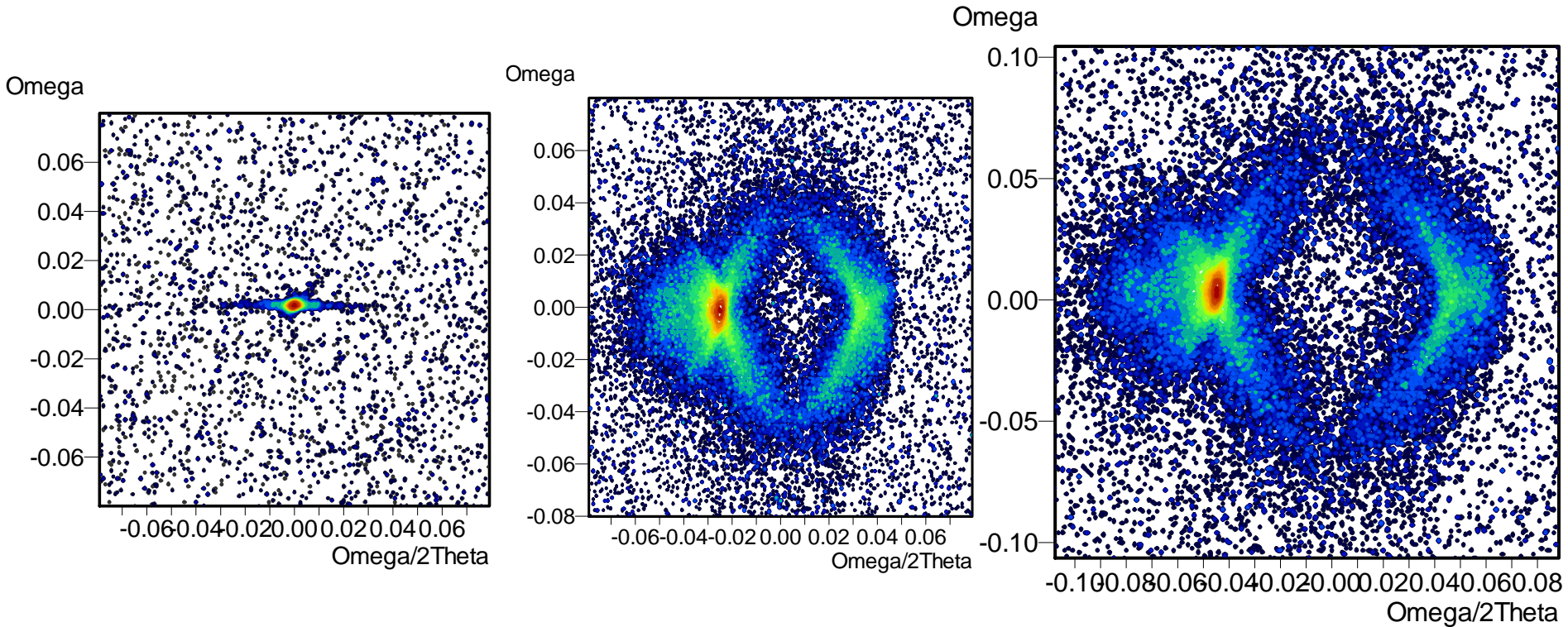


$$\varepsilon = \text{strain} = \Delta d/d$$

$$\sigma = \text{stress} = \varepsilon \times E$$



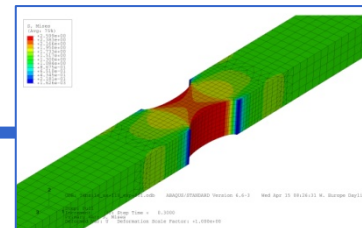
Mechanical Testing: In-situ Tensile Tests



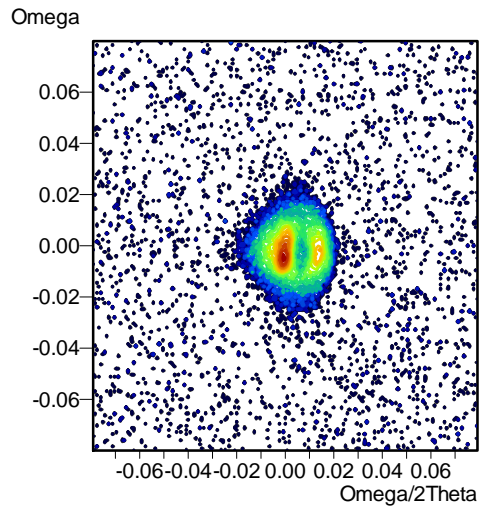
0N

4N

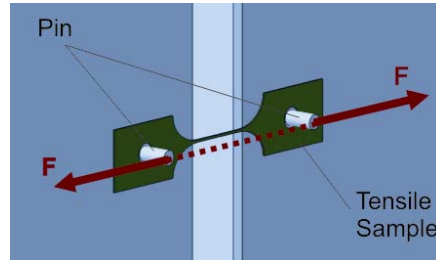
6N



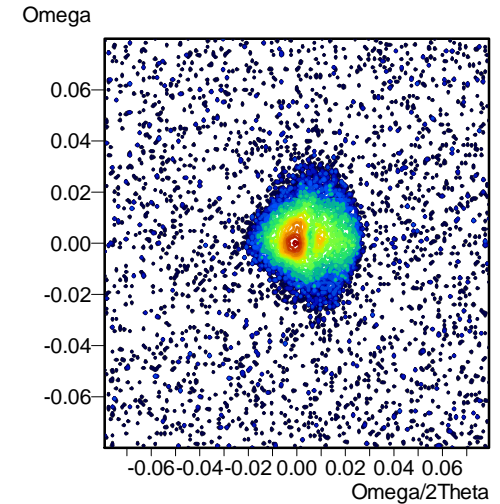
Mechanical Testing: In-situ Tensile Tests



Initial load: 1N



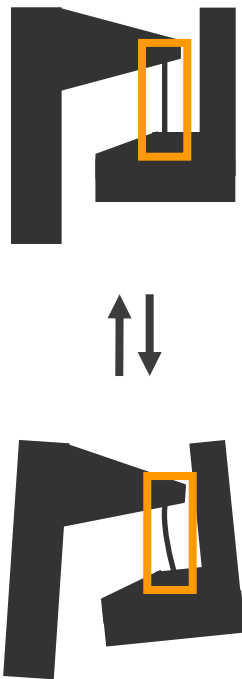
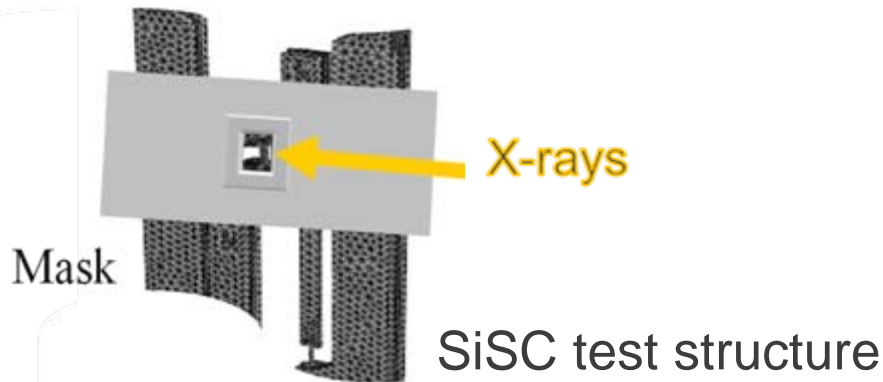
Loading to 6N
+ Relaxation



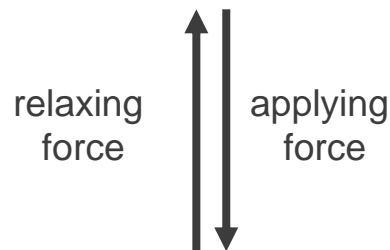
Final load: 1N

Bending Tests on SiSC beams

HRXRD investigations and simulations

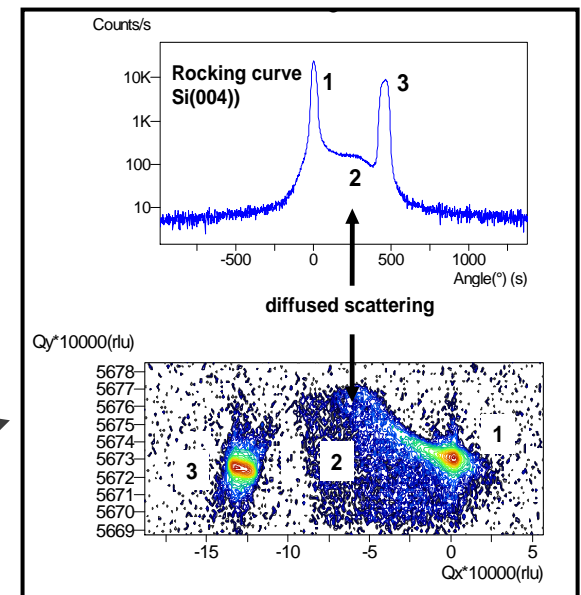
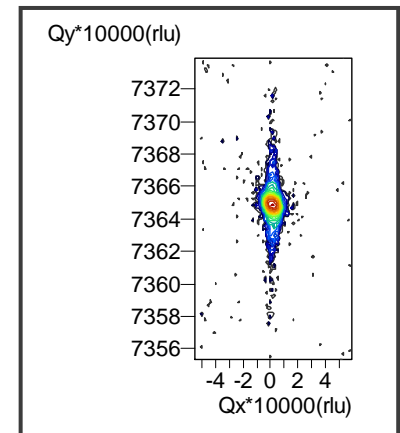


1. Relaxed structure
(low strain)

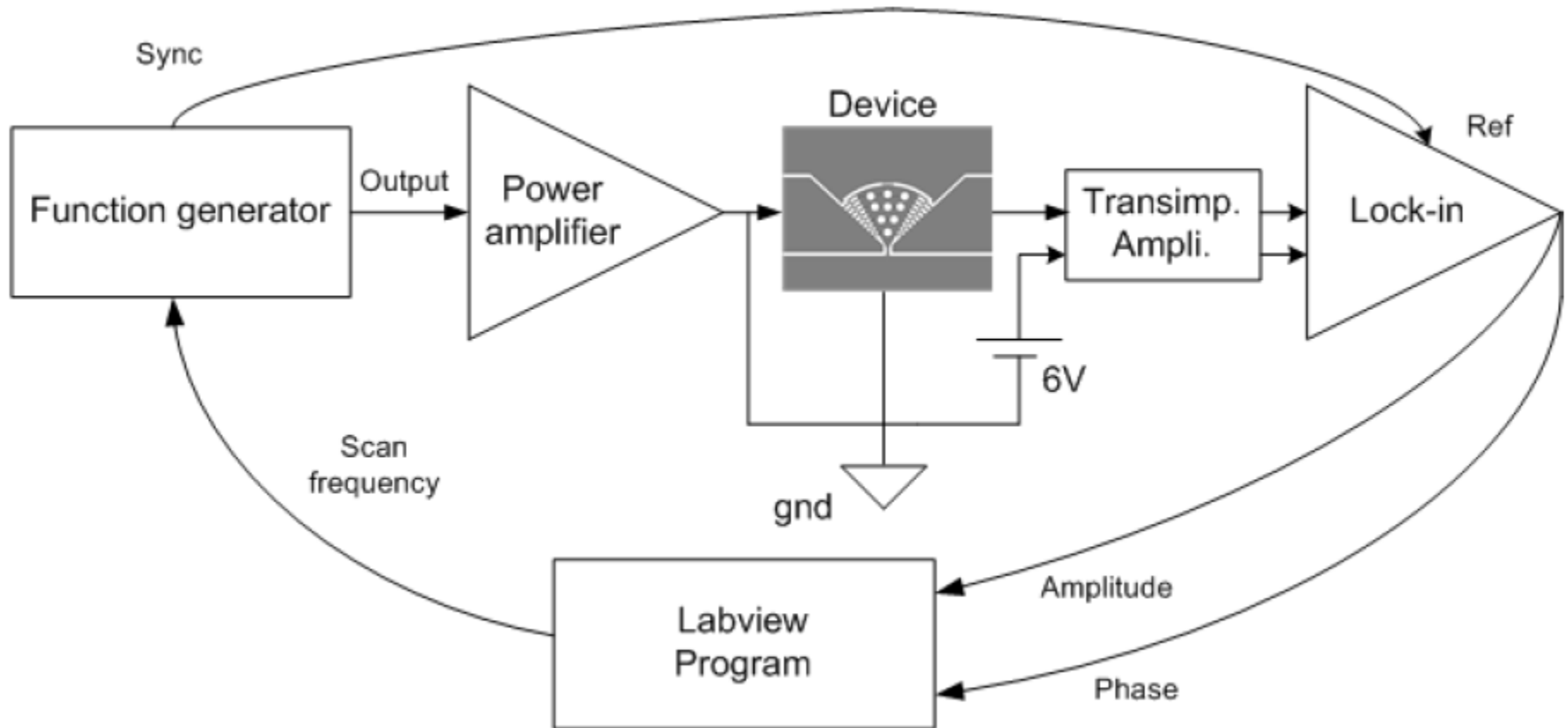


2. Bended structure
(high strain)

RC and RSMs

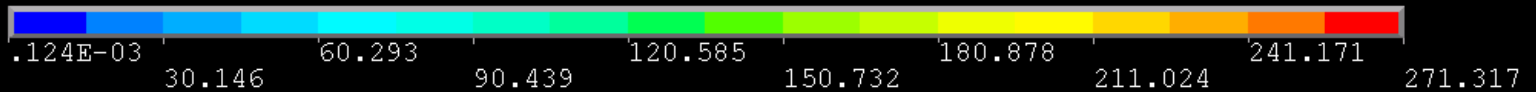
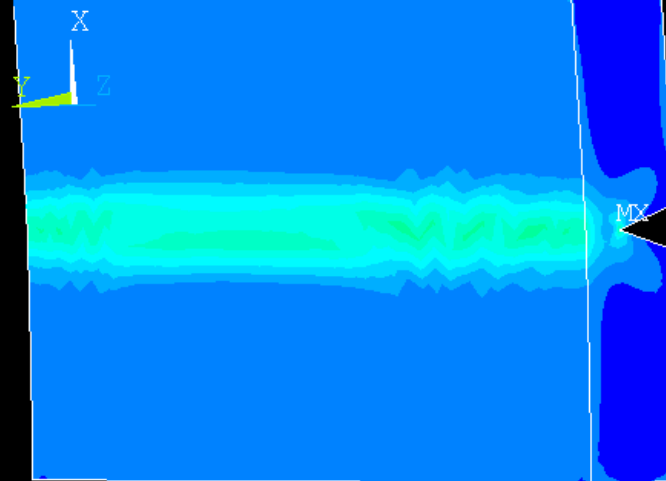


Scheme of the electrical set-up

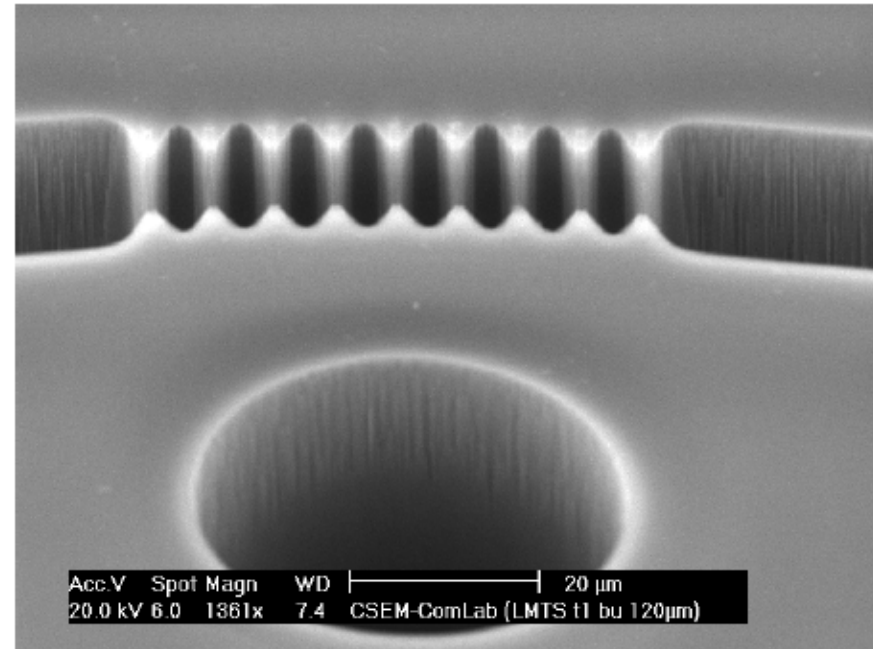
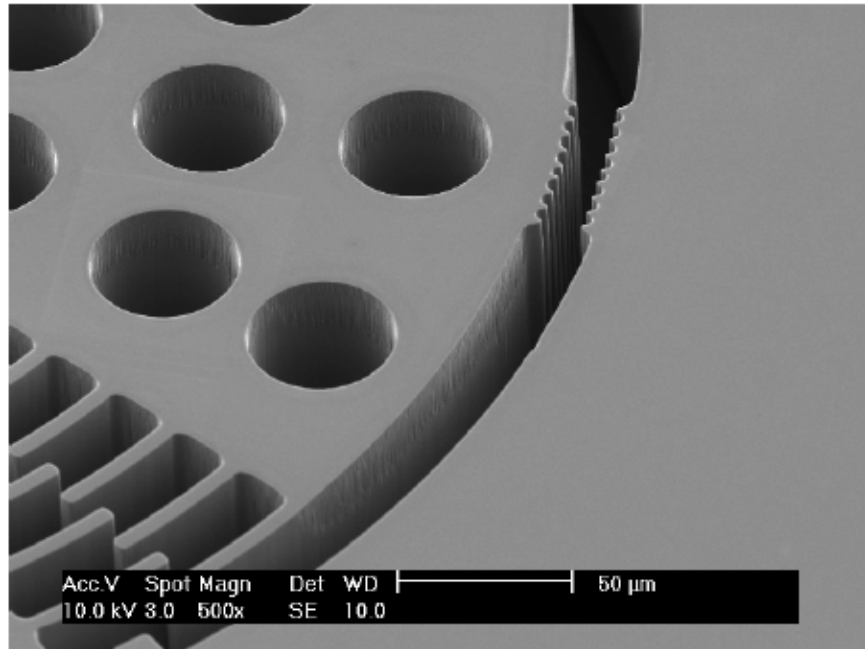


NODAL SOLUTION

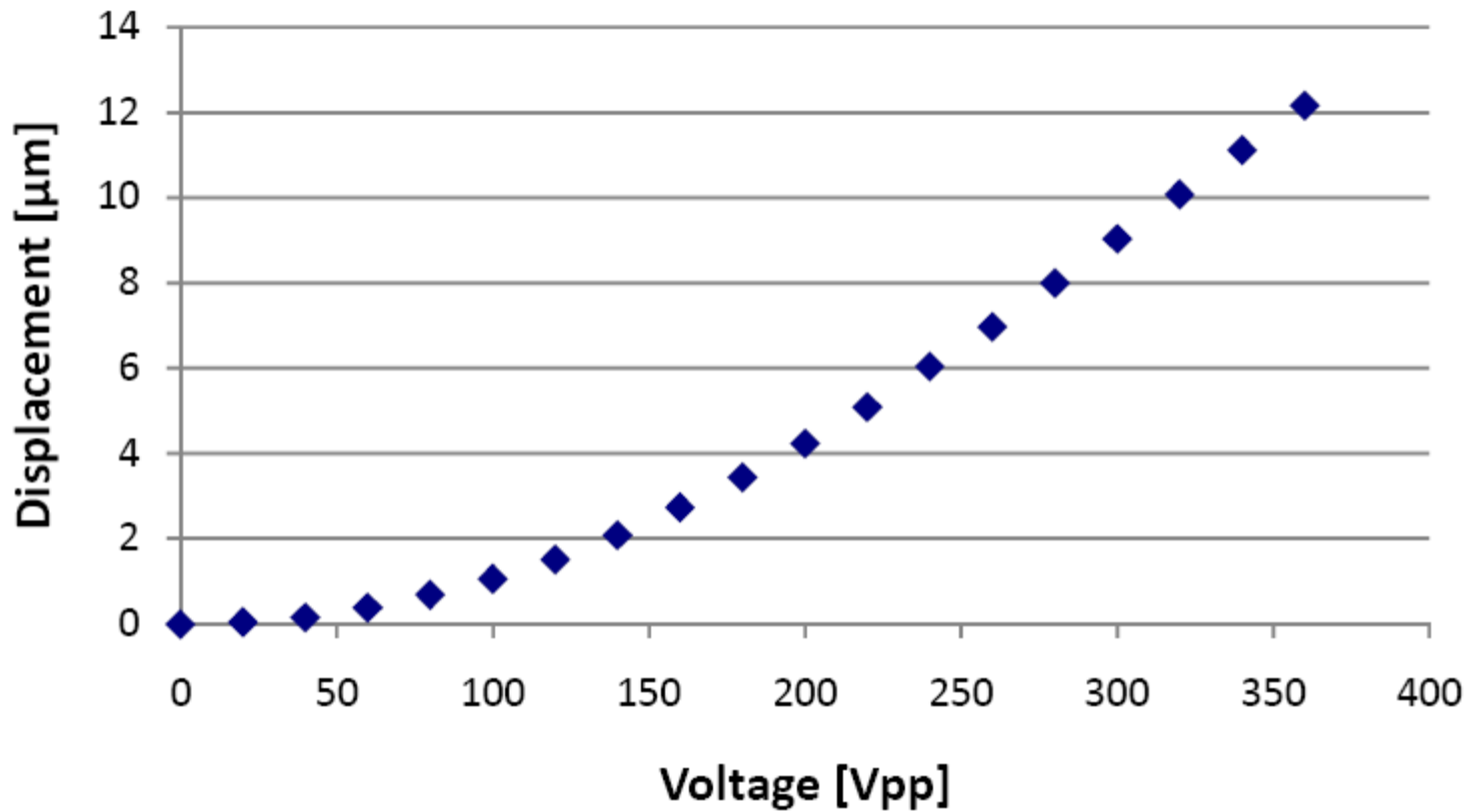
STEP=1
SUB =1
TIME=1
SINT (AVG)
DMX =1.107
SMN =.124E-03
SMX =271.317



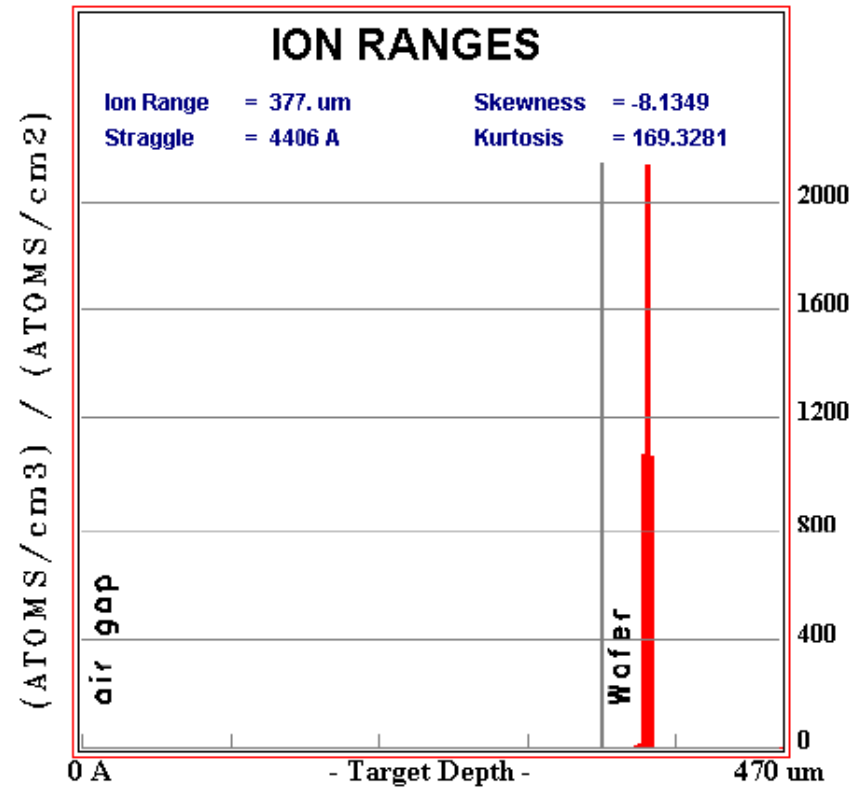
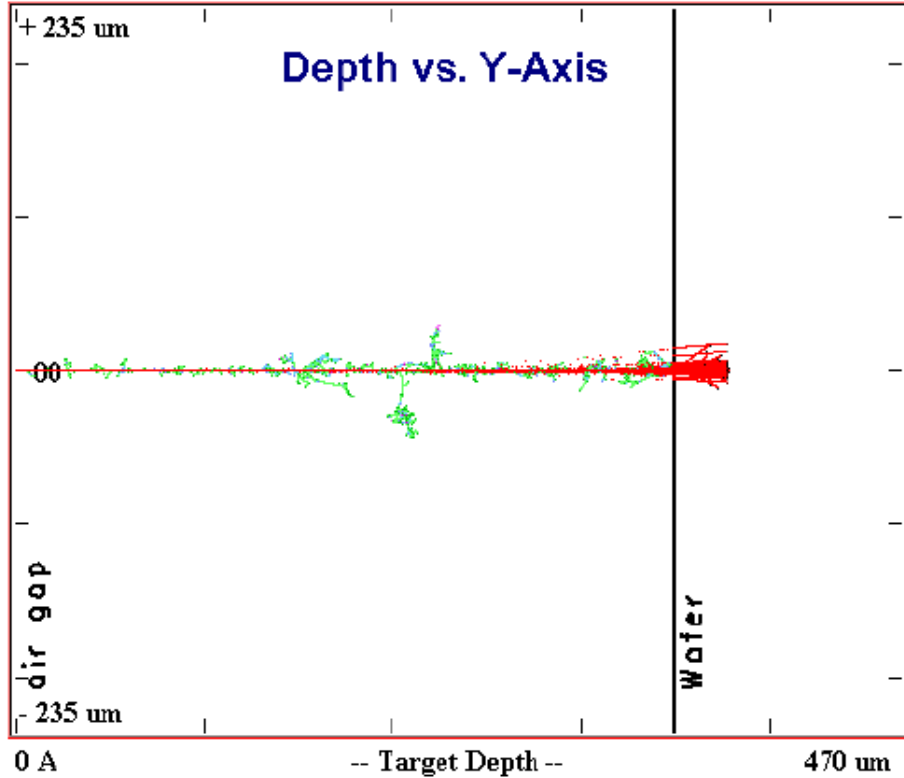
Silicon test device



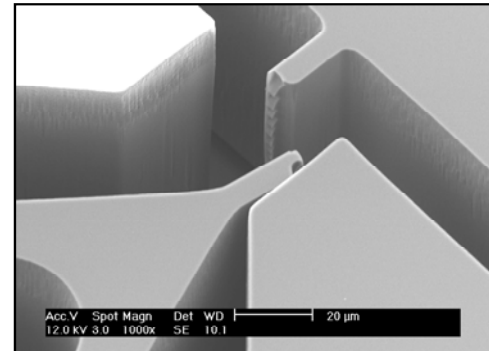
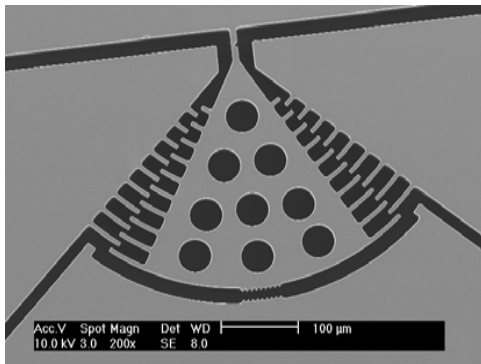
Mechanical Testing



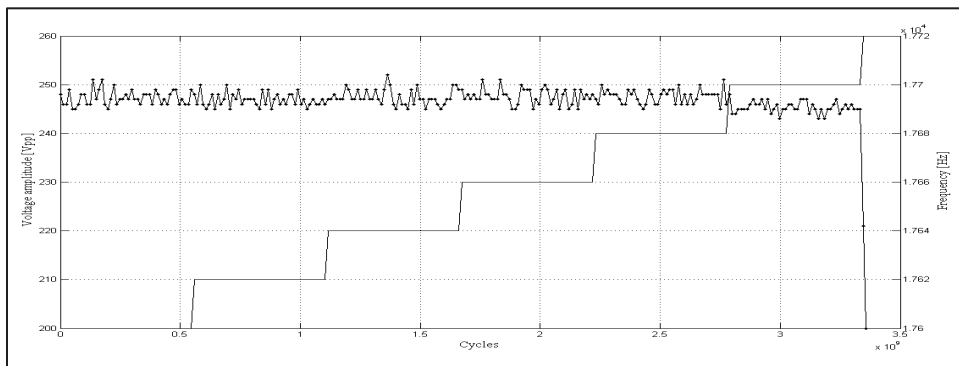
Radiation Damage



Mechanical Testing: High Cycle Fatigue

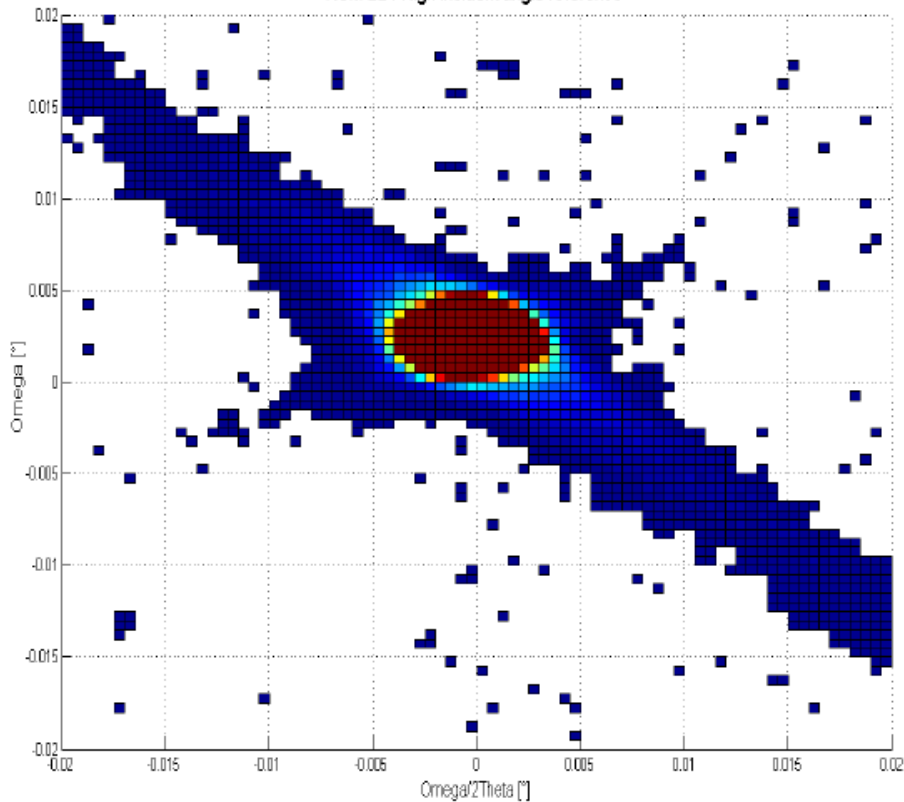


Accelerated aging of MEMS by high cycle fatigue.

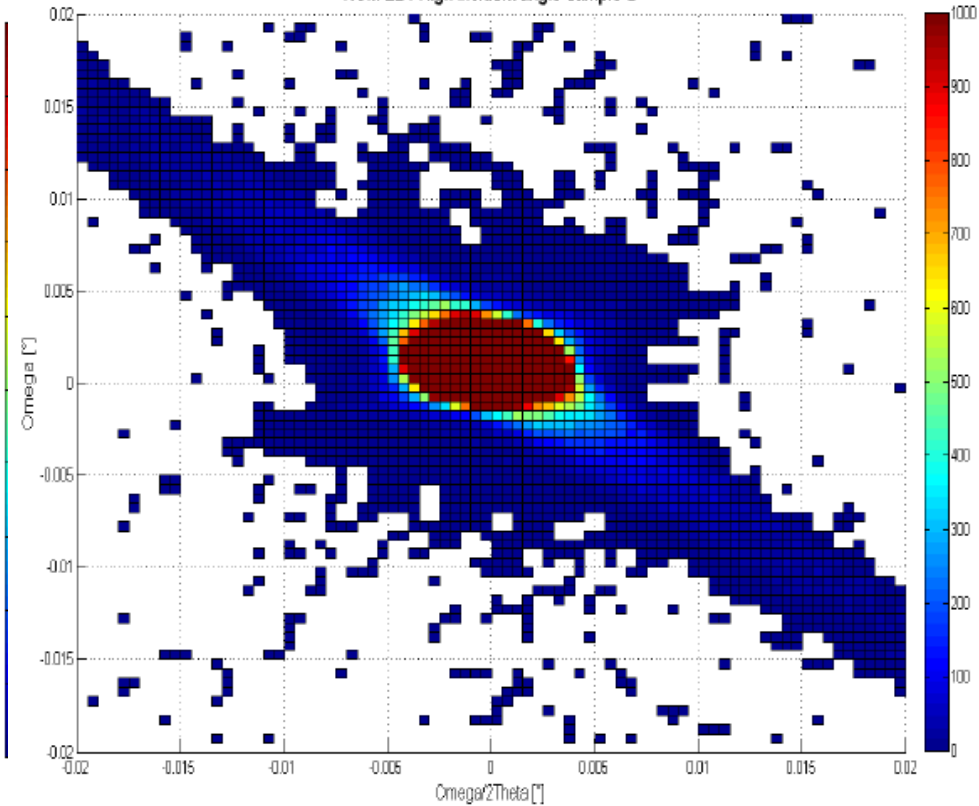


Radiation Damage

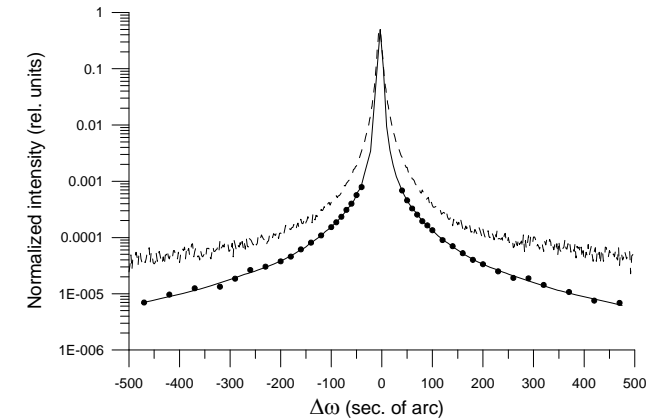
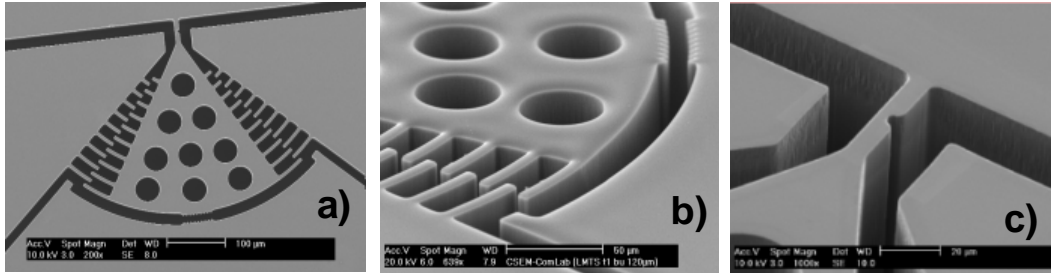
RSM 224 High incident angle reference



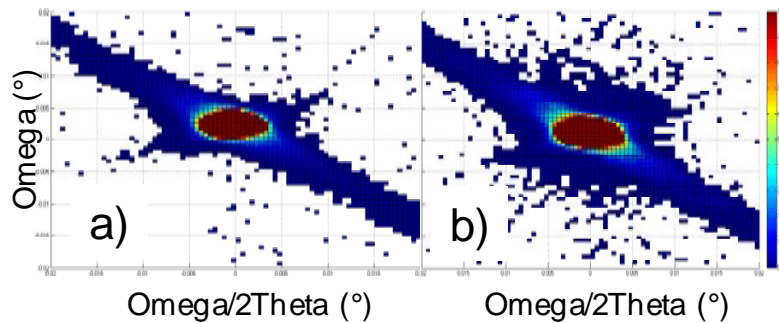
RSM 224 High incident angle sample B



Aging: Radiation Damage

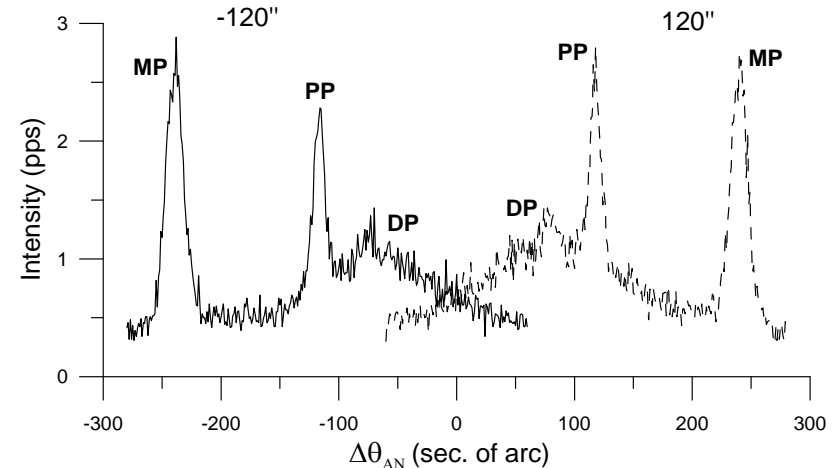


RSMs

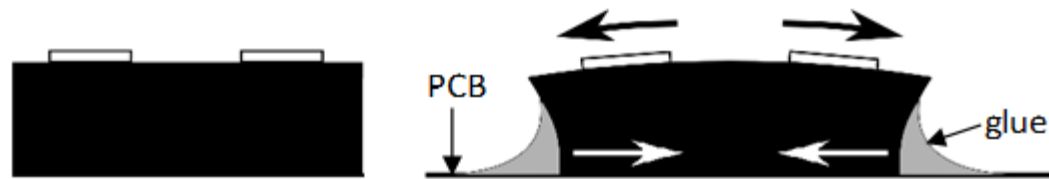


Wide TCD-spectra obtained at positions of the specimen = $-120''$ (solid line) and $= 120''$ (dashed line).

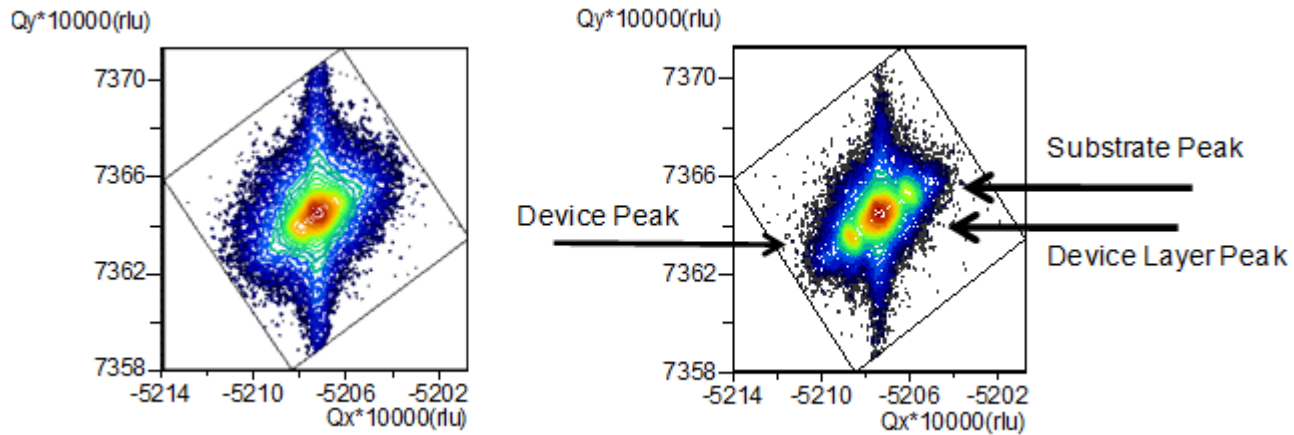
The experimental (dots) and fitted (solid line) TCD intensity curves. Dashed line is the double-crystal rocking curve (for comparison).



Packaging



Scheme of a chip (a) before bonding and (b) after bonding



RSM on the Si(224) reflection at high incident angle



EUCEMAN

European Center for
Micro- and Nanoreliability

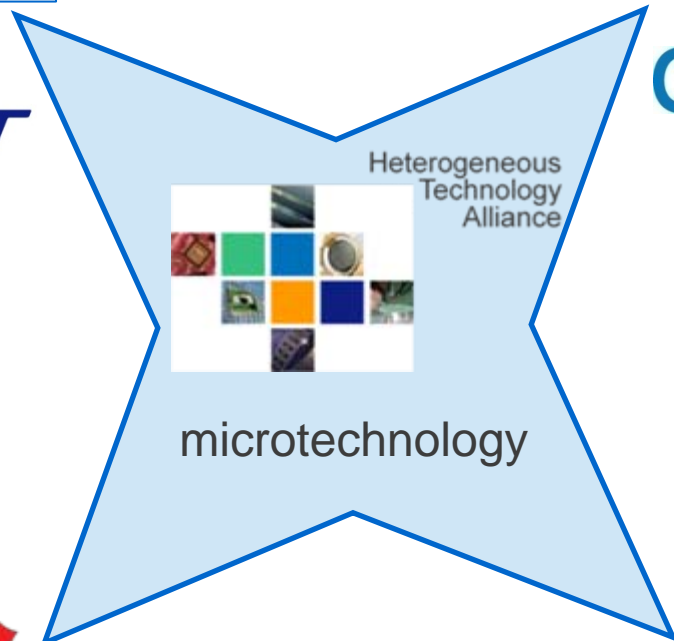


The Joint Reliability Team

EUCEMAN – European Center for Micro and Nanoreliability



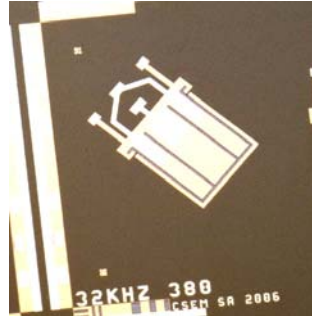
csem



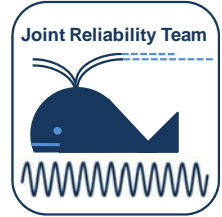
Fraunhofer
Verbund
Mikroelektronik

WALES « WAfer Level Encapsualtion for micro-Systems »

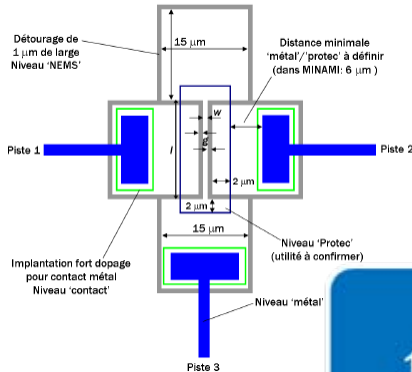
Piezoelectric Resonator
(20kHz – 1MHz)



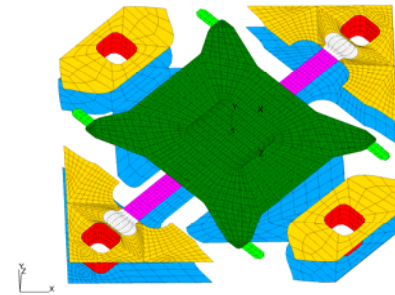
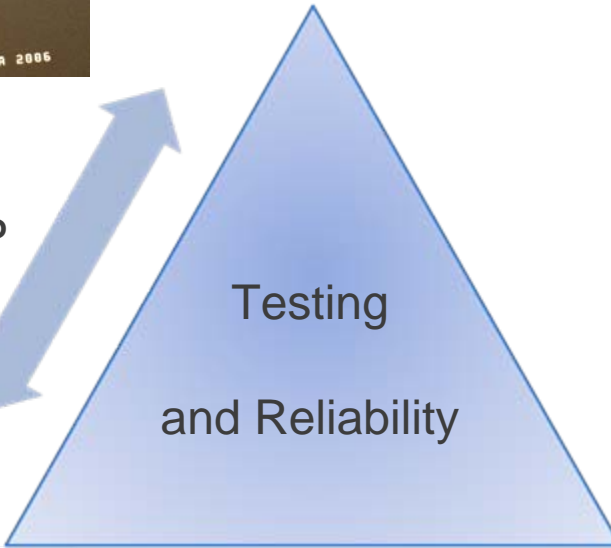
CSEM:
1) Fabrication
2) WLP
3) Testing



Capacitive Resonator
(100kHz – 10MHz)



WLP



CEA-LETI:
1) Fabrication
2) WLP
3) Testing

Fraunhofer Gesellschaft:
1) Hermeticity
2) Testing

Acknowledgements



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Andreas Schifferle

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Dr. Claude Müller
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Prof. Enver Mukhamadzhonov
Prof. Eduardo Mazza

Thank you for your attention !